

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	355	(SOI or "silicon on insulator") same (mask\$4 or pattern\$4) same oxidiz\$4	USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/05/02 14:47
L2	18965	(SOI or "silicon on insulator")	USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/05/02 14:33
L3	625	(SOI or "silicon on insulator") same oxidiz\$4 same(etch\$3 or remov\$3)	USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/05/02 14:34
L5	1538	(SOI or "silicon on insulator") and (mask\$4 or pattern\$4) and oxidiz\$4 and anneal\$3 and etch\$3	USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/05/02 14:42
L6	1167	5 and (trench or via or opening)	USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/05/02 14:42
L7	73	5 and (trench or via or opening) and liner	USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/02 14:46
L8	131	(SOI or "silicon on insulator") same (mask\$4 or pattern\$4) same oxidiz\$4 same thickness	USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/05/02 14:47